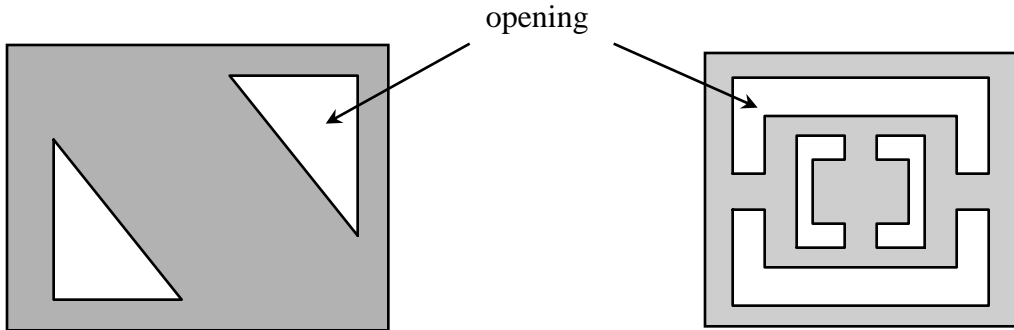


1. Please determine if the following patterns can be fully undercut or not?



2. The feature depicted in the figure below is patterned onto a (100) wafer surface with an ideal mask. The wafer is then etched in a solution with infinite selectivities for (100) over (111), and (110) over (111) for a long period of time.

- (a) Draw the top view and side view (at cross section AA) of the final etched pattern, indicating the angles between all sides as well as the length of the sides.
- (b) Now, assume a finite selectivity of 40 for (100) over (111), repeat (a)

